

02/10/2009

Reply under 37 C.F.R. 1.116
Expedited Procedure
Technology Center 1792

Confirmation no. 3423

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	DE BOER	Examiner:	Lund, J.
Serial No.:	10/537,363	Group Art Unit:	1792
Filed:	June 2, 2005	Docket No.:	US020527US
Title:	SYSTEM AND METHOD FOR SUPPRESSION OF WAFER TEMPERATURE DRIFT IN COLD-WALL CVD SYSTEMS		

SUPPLEMENTAL RESPONSE TO FINAL OFFICE ACTION

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Customer No. 65913

Dear Sir:

In response to the Final Office Action dated November 19, 2008 and in anticipation of the withdrawal of the Final Office Action in view of the Response dated January 19, 2008 (hereby incorporated by reference in its entirety), Applicant submits this supplemental response adding new claims 15-19.

A complete listing of the Claims and Remarks/Arguments follow.

Authorization is given to charge/credit Deposit Account 50-0996 (NXPS.441PA) all required fees/overages to enter this paper.